

ABSTRACT

Aspects of the present invention provide for a novel photomask for patterning features for an integrated circuit, the photomask including masked features having interior nonprinting windows. In some embodiments, the interior nonprinting window is an alternating phase shifter, while the area surrounding the masked features transmits light unshifted. In other embodiments, the interior nonprinting window transmits light unshifted, while the area surrounding the masked features is an alternating phase shifter. Thus any arrangement of features can be patterned with no phase conflict.